## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of Atty. Ref.: 4662-138

SHAHAB et al Conf. No.: 9555

Serial No. 10/565,505 Group: 1795

Filed: July 6, 2006 Examiner: Johnson

For: IMMERSION LITHOGRAPHY PROCESSES USING PHOTORESIST

COMPOSITIONS WHICH INCLUDE DISSOLUTION INHIBITORS

February 6, 2009

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

## AMENDMENT

Sir:

The following comments and amendments are intended to be fully responsive to the Official Action dated October 6, 2008, petition being hereby made for one (1) month time extension up to and including February 6, 2009.

Pursuant to 37 CFR §1.121, each section of the subject Amendment (e.g., Claim Amendments, Specification Amendments, Drawing Amendments and Remarks) as may be appropriate to the issues raised in the Official Action to which this paper responds, begins on a separate page. Changes to the original text, claims and the like are shown by striking through language to be deleted and underlining of language to be added.